

REMARKS

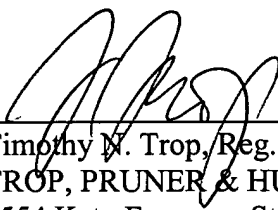
The Examiner applies Hallock, which the Examiner suggests penetrating a vapor into a photoresist and Verhaverbeke, which teaches drying the photoresist out. These are completely inconsistent approaches. One cannot combine a reference which supposedly teaches wetting the photoresist with vapor with a reference which teaches the opposite thing, namely, drying the photoresist. There is simply no way to combine the two references because their teachings lead in opposite directions and their combination could only result in nothing but confusion.

Since it is conceded that Hallock alone does not teach the claimed invention and, certainly, Verhaverbeke alone cannot teach the claimed invention, reconsideration would be appropriate, particularly in view of the fact that there is no way to combine the references and there could be no rationale to do so.

The suggestion that it would be good to use Verhaverbeke to dry the material goes directly contrary to what Hallock says. There is no reason to dry the photoresist before reflowing the photoresist because doing so would be contrary to the aims of the claimed invention and, according to the Examiner, contrary to the aims of Hallock. That is, the vapor that Hallock allegedly just penetrated into the photoresist would then be driven out if Verhaverbeke's process were also used.

Respectfully submitted,

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